

DUAL SUBSTRATE LOADLOCK PROCESS EQUIPMENT

ABSTRACT

1 One embodiment relates to a loadlock having a first support structure therein to
2 support one unprocessed substrate and a second support structure therein to support one
3 processed substrate. The first support structure is located above the second support
4 structure. The loadlock includes an elevator to control the vertical position of the support
5 structures. The loadlock also includes a first aperture to permit insertion of an
6 unprocessed substrate into the loadlock and removal of a processed substrate from the
7 loadlock, as well as a second aperture to permit removal of an unprocessed substrate
8 from the loadlock and insertion of a processed substrate into the loadlock. A cooling plate
9 is also located in the loadlock. The cooling plate includes a surface adapted to support a
10 processed substrate thereon. A heating device may be located in the loadlock above the
11 first support structure.

Figure 1



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